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## **Electronic Supplementary Information (ESI)**



Fig. S1 SEM images of a) air- $In_2O_3$  and b)  $H_2$ - $In_2O_3$ .



**Fig. S2** Survey XPS spectra of air- $\ln_2O_3$  and  $H_2$ - $\ln_2O_3$  (a). In 3d core level XPS spectra of air- $\ln_2O_3$  and  $H_2$ - $\ln_2O_3$  (b). XPS spectra of 0 1s peak of air- $\ln_2O_3$  (c) and  $H_2$ - $\ln_2O_3$  (d). Black lines are the experimental XPS data, which are further fitted into two peaks (shown by red lines).

The XPS has been employed to detect the chemical states of air- and  $H_2$ - $In_2O_3$  samples. Only O, In and C (used as reference) signals appear in XPS survey acquired from air- and  $H_2$ - $In_2O_3$  (Fig. S2 a). As shown in Fig. S2 b In 3d peaks of  $H_2$ - $In_2O_3$  are very closed to the In 3d peaks of air- $In_2O_3$ . However, after hydrogen treatment In 3d peaks at lower binding energy could be mainly ascribed to oxygen vacancies.<sup>1, 2</sup> Fig. S2 c and d presents the XPS spectrum for O 1s airand  $H_2$ - $In_2O_3$  respectively and each O 1s curve can be fitted into two peaks. In both samples, highest binding energy peak located at 529 eV is corresponded to indium oxygen bond (In-O). In air- $In_2O_3$  the peak at 531.2 eV can be attributed to the O<sup>2-</sup> ions in the oxygen deficient region or to the surface adsorbed oxygen.<sup>3</sup> Whereas, in  $H_2$ - $In_2O_3$  the peak centered at 531.4 eV can be assigned to the oxygen defects.<sup>4</sup> Furthermore, In 3d and O 1s regions evidenced no significant differences in the particle surface of air- and  $H_2$ - $In_2O_3$ . This could be the reason that the green emission intensity is lower than blue emission.



**Fig. S3** (a) FT-IR spectra of  $H_2$ - $In_2O_3$  at 400 °C for 12 h and (b and c) after oxidative treatment at 200 °C for 6 h and 400 °C for 12 h, respectively. After oxidative treatment (from top to bottom b and c), there is a continuous decrease in IR absorption signals.

FT-IR spectroscopy is a useful technique to monitor the CB and shallow state electrons in n-type semiconductors. According to Drude theory the resonance frequency of electrons depends upon the number of free electrons ( $e^{-}$ ) N. The absorbance at a particular wavelength ( $\lambda$ ) is proportional to number of electron (N) in conduction band.

$$A(\lambda) \sim N$$
 eq (1)

The increased absorption in IR spectra (Fig. 3S a) can directly attributed to the CB and shallow state electrons in H<sub>2</sub>-In<sub>2</sub>O<sub>3</sub>, as a result of reducing atmosphere. In order to test this hypothesis the respective sample (H<sub>2</sub>-In<sub>2</sub>O<sub>3</sub>) was oxidized at 200 °C for 6 h and 400 °C for 12 h (Fig. 3S b and c). The intensity of broad absorption in IR spectra decreased upon oxygen adsorption. The electrons in CB and shallow state combine with hole and cause recombination process. However adsorbed O<sub>2</sub> can act as an electron sink and prevent such recombination process.<sup>5</sup> The adsorbed O<sub>2</sub> clearly affect or decrease the CB electrons and represent inactive IR species. Thus, the broad absorbance is quenched upon introduction of oxygen, which acts as an excellent electron (e<sup>-</sup>) scavenger.



Fig. S4 Methyl orange degradation under irradiation > 400 nm with an optical power density 150 mW cm<sup>-2</sup> using H<sub>2</sub>O<sub>2</sub> as an oxidant. For blank experiment all parameters are same except sample addition.

## References

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